

Notice of References Cited	Application/Control No. 10/534,199	Applicant(s)/Patent Under Reexamination ASPAR ET AL.	
	Examiner Bradley K. Smith	Art Unit 2894	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Bernard Terreault "Hydrogen blistering of silicon: Progress in fundamental understanding" Phys. Stat. Sol. (a) 204 No. 7, pp2129-2184 (2007)
	V	Duo et al. "Comparison between the different implantation orders in H+ and He+ coimplantation" J. Phys. D: Appl. Phys. 34 (2001) pp 477-482
	W	Weldon et al. "Mechanism of silicon exfoliation induced by hydrogen/helium co-implantation" Applied Physics Letters vol. 73 number 25, pp 3721-3723
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.